What Is Claimed Is:

- 1. An array substrate for a reflective liquid crystal display device, comprising:
- a substrate;
- a gate line on the substrate;
- a data line crossing the gate line to define a pixel region;
- a plurality of convex patterns in the pixel region, each convex pattern having a cross-section with a semicircular shape;

an organic insulating layer on the plurality of convex patterns, the organic insulating layer being in between the gate line and the data line;

- a thin film transistor connected to the gate line and the data line;
- an inorganic insulating layer on the organic insulating layer; and
- a reflective layer on the inorganic insulating layer, the reflective layer having unevenness corresponding to the plurality of convex patterns.
- 2. The substrate according to claim 1, wherein the inorganic insulating layer covers the thin film transistor.
- 3. The substrate according to claim 1, wherein the thin film transistor includes a gate electrode, a first semiconductor layer, a source electrode, and a drain electrode.
- 4. The substrate according to claim 3, wherein the first semiconductor layer includes an active layer of intrinsic amorphous silicon and an ohmic contact layer of impurity-doped amorphous silicon.

16 DC:50250032.1

- 5. The substrate according to claim 3, wherein the organic insulating layer is in between the gate electrode and the first semiconductor layer.
- 6. The substrate according to claim 5, wherein the inorganic insulating layer includes a drain contact hole exposing the drain electrode.
- 7. The substrate according to claim 6, wherein the reflective layer is connected to the drain electrode through the drain contact hole.
- 8. The substrate according to claim 3, further comprising a second semiconductor layer between the organic insulating layer and the data line, the second semiconductor layer extending from the first semiconductor layer.
- 9. The substrate according to claim 3, further comprising an island shaped metal pattern on the organic insulating layer over a portion of the gate line to form a storage capacitor.
- 10. The substrate according to claim 9, further comprising a third island shaped semiconductor layer between the organic insulating layer and the metal pattern, the third semiconductor layer having the same structure as the first semiconductor layer.
- 11. The substrate according to claim 1, wherein the organic insulating layer includes one of benzocyclobutene (BCB) and acrylic resin.
- 12. A method of fabricating an array substrate for a reflective liquid crystal display device, comprising:

forming a gate line on a substrate having a pixel region;

forming a plurality of convex patterns on the substrate in the pixel region, each convex pattern having a cross-section with a semicircular shape;

forming an organic insulating layer on the gate line and the plurality of convex patterns;

forming a data line on the organic insulating layer, the data line crossing the gate line;

forming a thin film transistor connected to the gate line and the data line; forming an inorganic insulating layer on the thin film transistor and the organic

insulating layer; and

forming a reflective layer on the inorganic insulating layer, the reflective layer having unevenness corresponding to the plurality of convex patterns.

- 13. The method according to claim 12, wherein the thin film transistor includes a gate electrode, a first semiconductor layer, a source electrode and a drain electrode.
- 14. The method according to claim 13, wherein the organic insulating layer is formed between the gate electrode and the first semiconductor layer.
- 15. The method according to claim 13, further comprising forming a second semiconductor layer between the organic insulating layer and the data line.
- 16. The method according to claim 15, further comprising forming an island shaped metal pattern on the organic insulating layer over a portion of the gate line.

- 17. The method according to claim 16, further comprising forming a third island shaped semiconductor layer between the organic insulating layer and the metal pattern.
- 18. The method according to claim 17, wherein the first semiconductor layer, the second semiconductor layer, and third semiconductor layer are simultaneously formed.
 - 19. An array substrate for a reflective liquid crystal display device, comprising: a substrate;
 - a gate line on the substrate;
 - a data line crossing the gate line to define a pixel region;
- a plurality of convex patterns in the pixel region, each convex pattern having a cross-section with a semicircular shape;

an organic insulating layer on the plurality of convex patterns, the organic insulating layer being in between the gate line and the data line;

- a thin film transistor connected to the gate line and the data line;
- a first semiconductor layer on the organic insulating layer in the pixel region; and
- a reflective layer on the first semiconductor layer, the reflective layer having unevenness corresponding to the plurality of convex patterns.
- 20. The substrate according to claim 19, wherein the thin film transistor includes a gate electrode, a second semiconductor layer, a source electrode, and a drain

electrode, and wherein the first semiconductor layer extends from the second semiconductor layer and the reflective electrode extends from the drain electrode.

20 DC:50250032.1